

**Amendments to the Specification:**

Please replace the heading on page 8, line 8, of the application as originally filed with the following amended heading:

**PROBLEMS TO BE SOLVES SOLVED BY THE INVENTION**

Please replace the paragraph beginning on page 9, line 18, and ending on page 9, line 25, of the application as originally filed with the following amended paragraph:

Referring to FIG. 5, it can be seen that the cleaning rate increases with increase in the  $\text{NF}_3$  gas concentration in the  $\text{Ar}/\text{NF}_3$  mixed gas. From this, it is derived that it is preferable to add  $\text{NF}_3$  to the  $\text{Ar}/\text{NF}_3$  mixed gas supplied to the remote plasma source 16C with the concentration ( $=\text{Ar}/(\text{Ar}+\text{NF}_3)$ ) of at least 5%, in order to achieve the cleaning rate of 500 nm/minute ~~nm/minute~~ or more under the pressure of 1200 Pa.